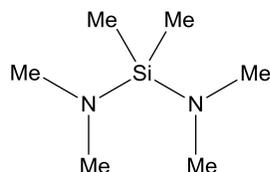


Catalog # 14-1530 Bis(dimethylamino)dimethylsilane, 96%

**Technical Notes:**

1. Used in the chemical vapor deposition of silicon nitride films, and also the atomic layer deposition of SiN_xC_y dielectric sealing layers using plasma-enhanced atomic layer deposition (PE-ALD).^{1,2,3,4}
2. Used as a reagent for silylation.^{5,6}

References:

1. *AIP Conference Proceedings*, **2015**, 1649(1, Irago Conference 2014), 41.
2. *Materials Science in Semiconductor Processing*, **2015**, 29, 139.
3. *Applied Surface Science*, **2010**, 257(4), 1196.
4. *Surface and Coatings Technology*, **2008**, 202(9), 1606.
5. *Microelectronic Engineering*, **1991**, 13(1-4), 47.
6. *Journal of Vacuum Science & Technology, B: Microelectronics and Nanometer Structures*, **1990**, 8(6), 1481.